Supplementary Material (ESI) for Journal of Materials Chemistry

Electronic Supplementary Information (ESI)

Realization of highly photoresponsive azobenzene-functionalized monolayers

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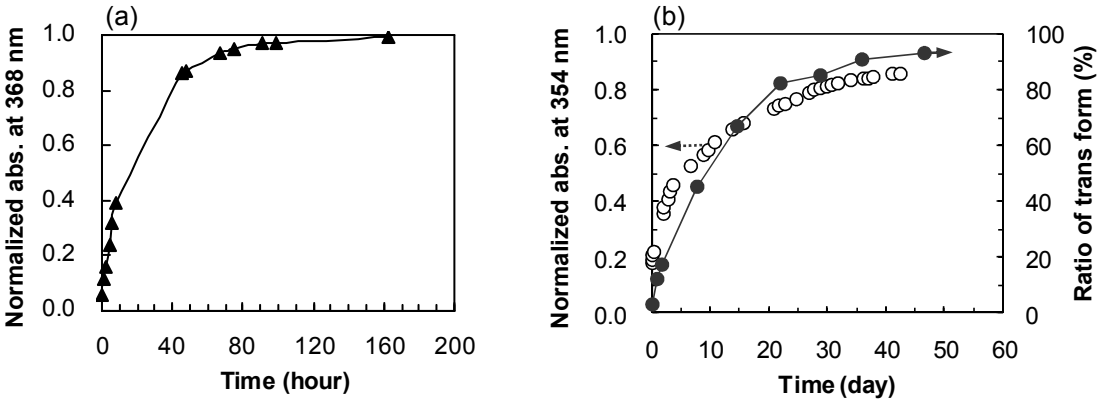

Fig. S1 Changes in the normalized absorbance at λ_{max} of π–π^* band of (a) MeSH and (b) EtSH in dichloromethane as a function of dark incubation after UV light irradiation. The ratio of the trans form of EtSH was obtained from ^{1}H NMR data (in CD_2Cl_2).

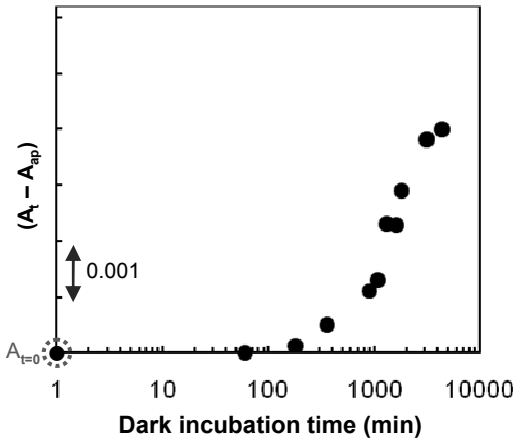

Fig. S2 Changes in (A_t–A_{ap}) of cis-EtSH SAMs as a function of thermal cis-to-trans isomerization time after UV light irradiation. A_{ap} and A_t correspond to absorbance at λ_{max} of as-prepared SAMs and after dark incubation for time (t), respectively.